

Fig. 1

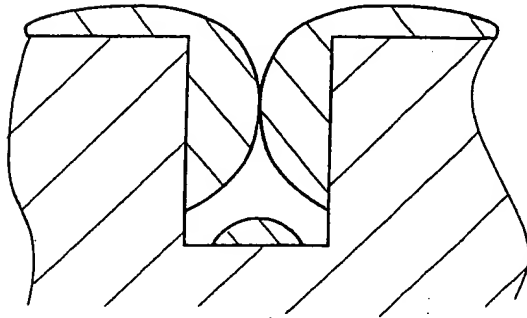


Fig. 2A

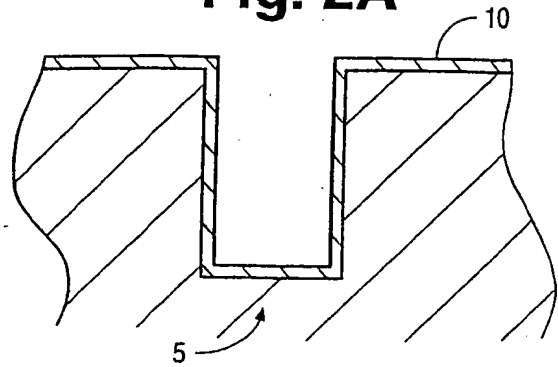


Fig. 2B

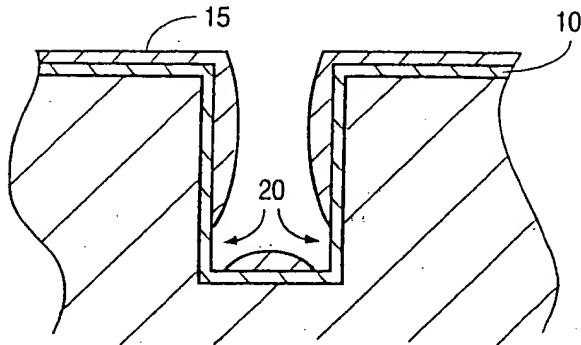


Fig. 2C

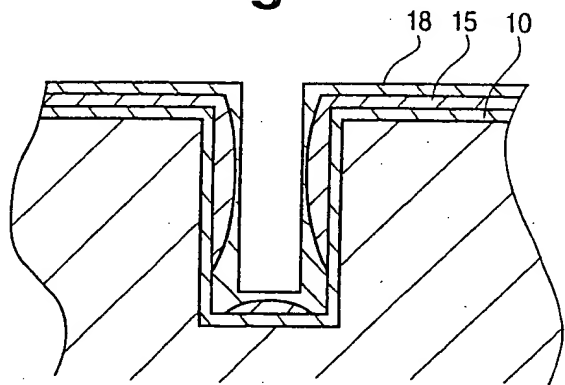


Fig. 2D

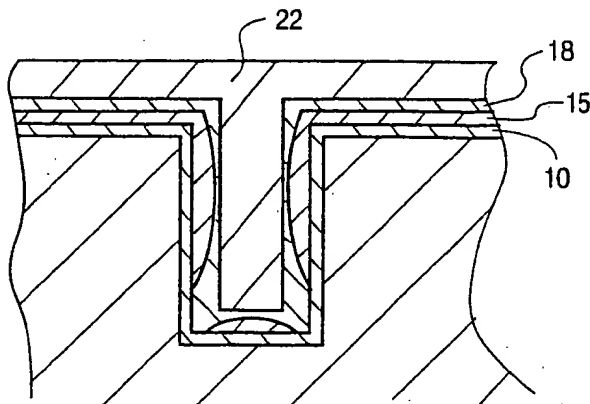
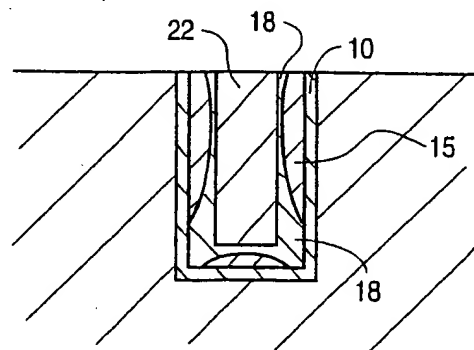
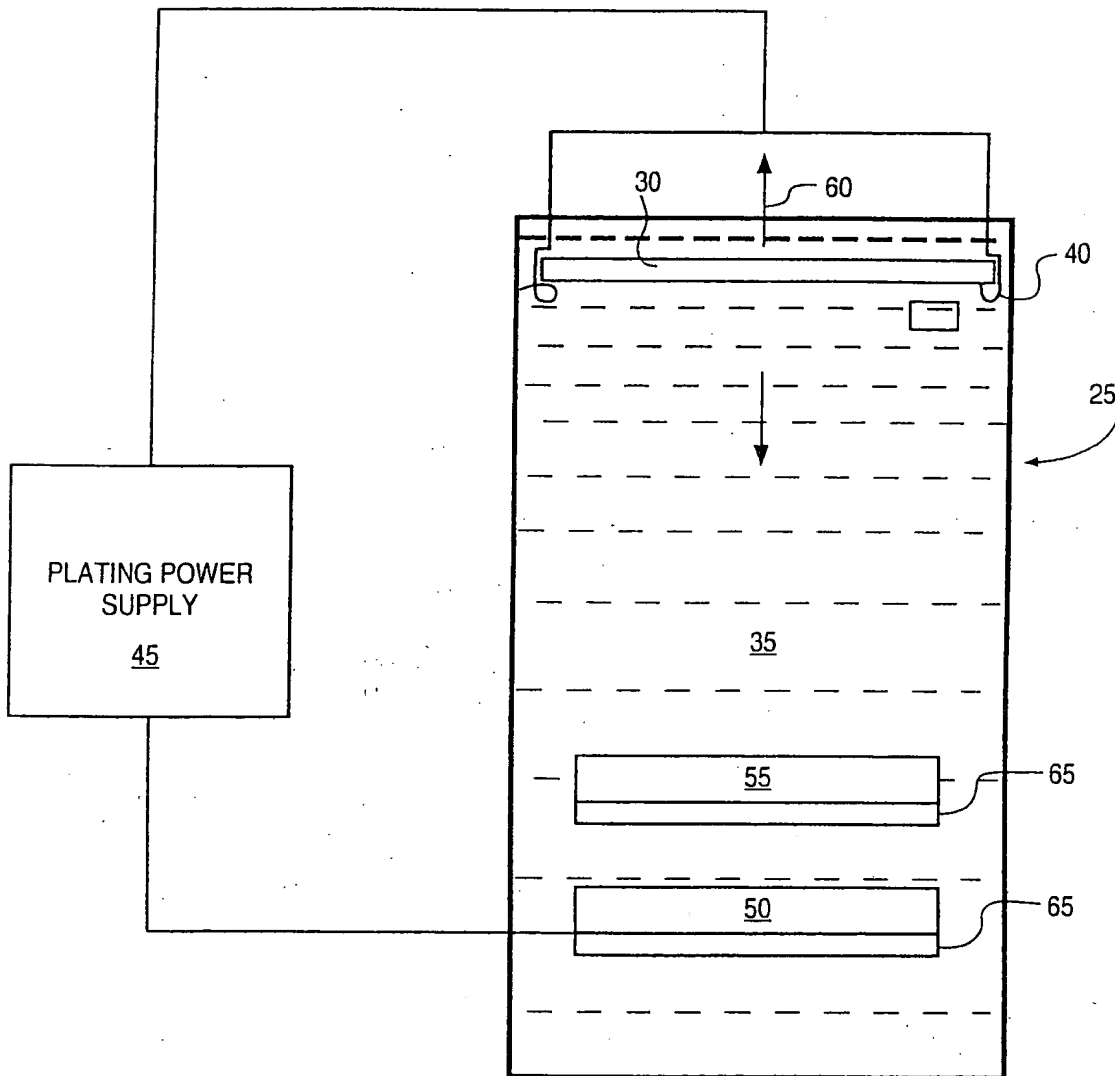


Fig. 2E

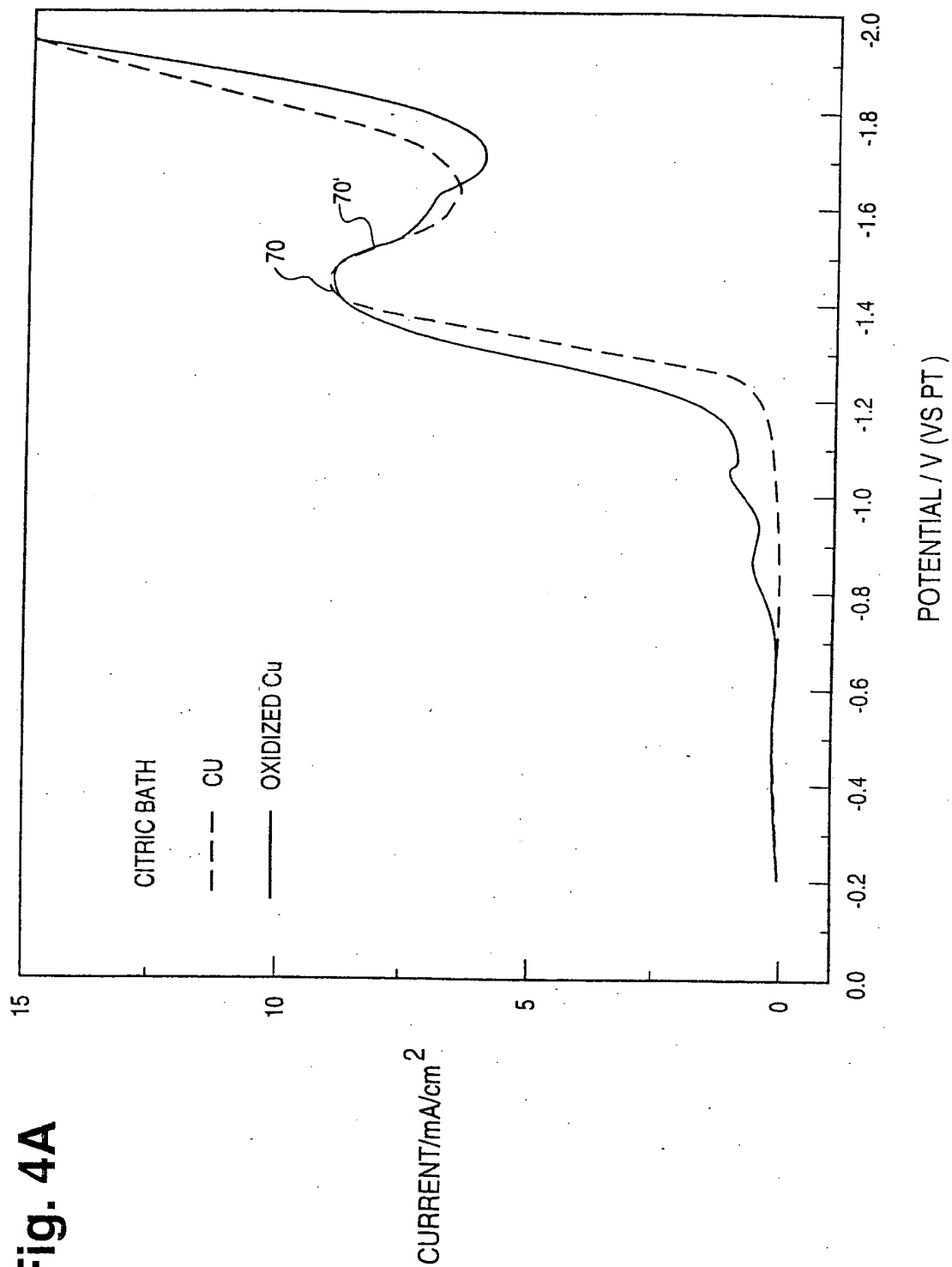


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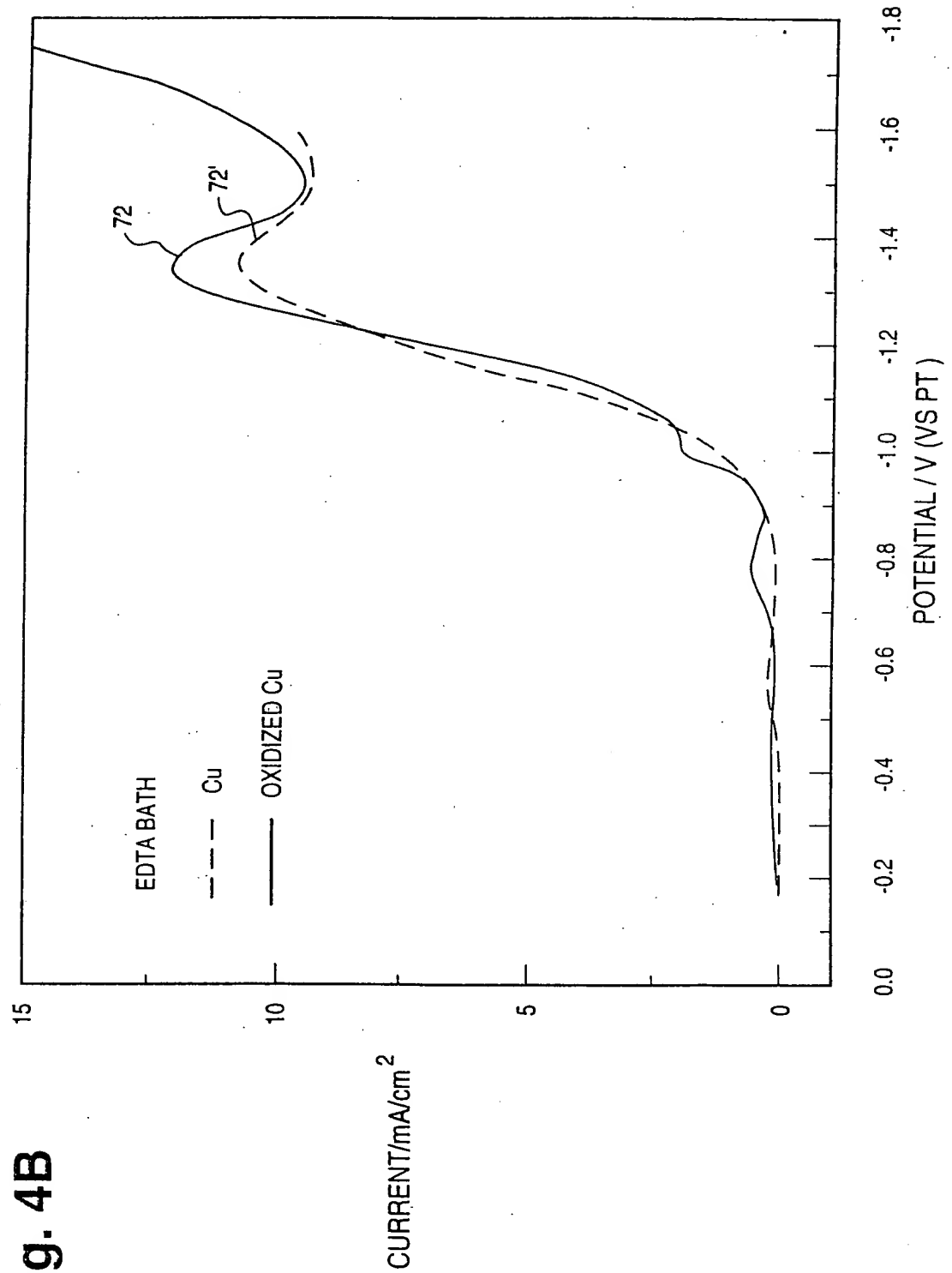
Fig. 3



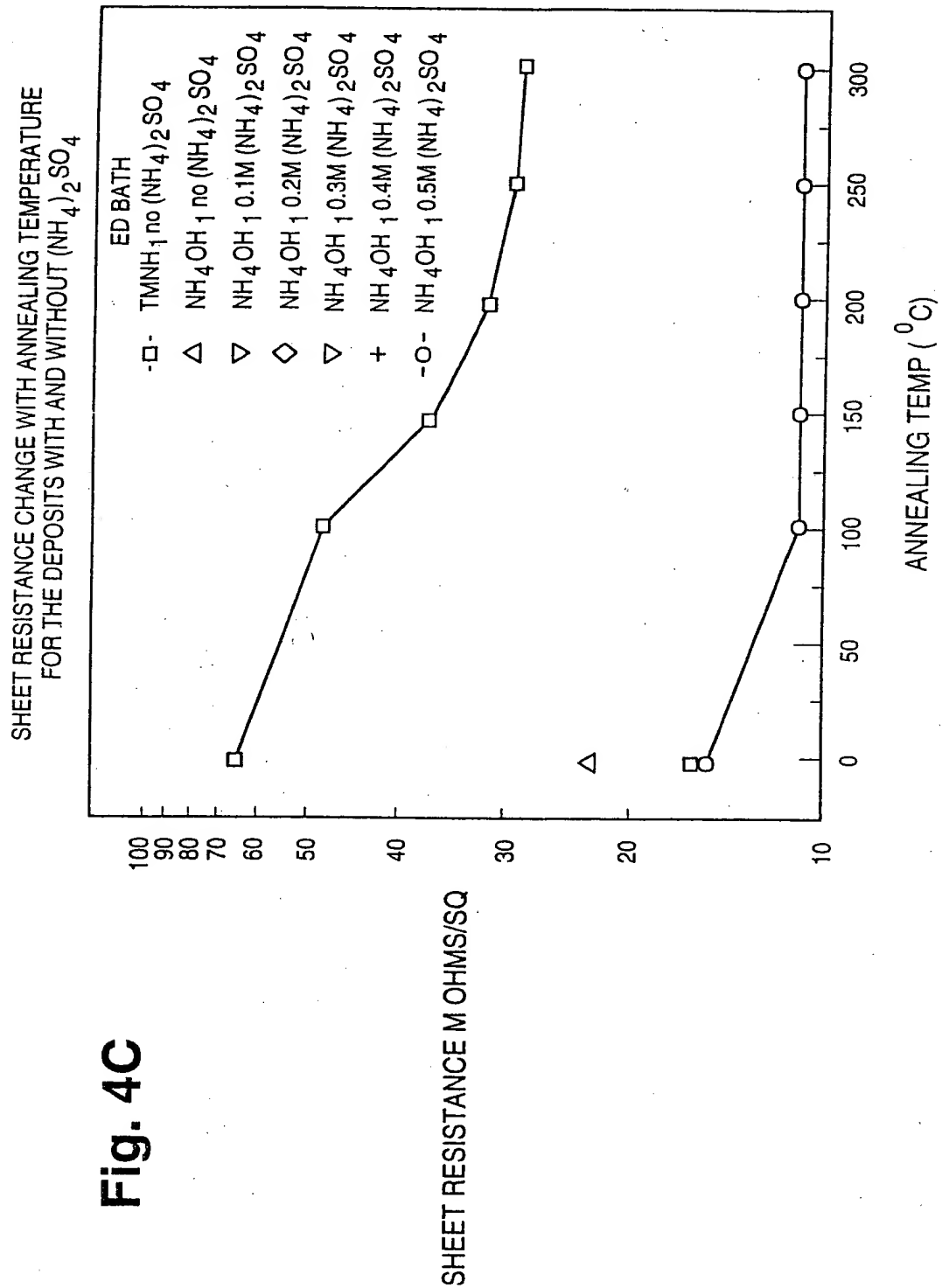
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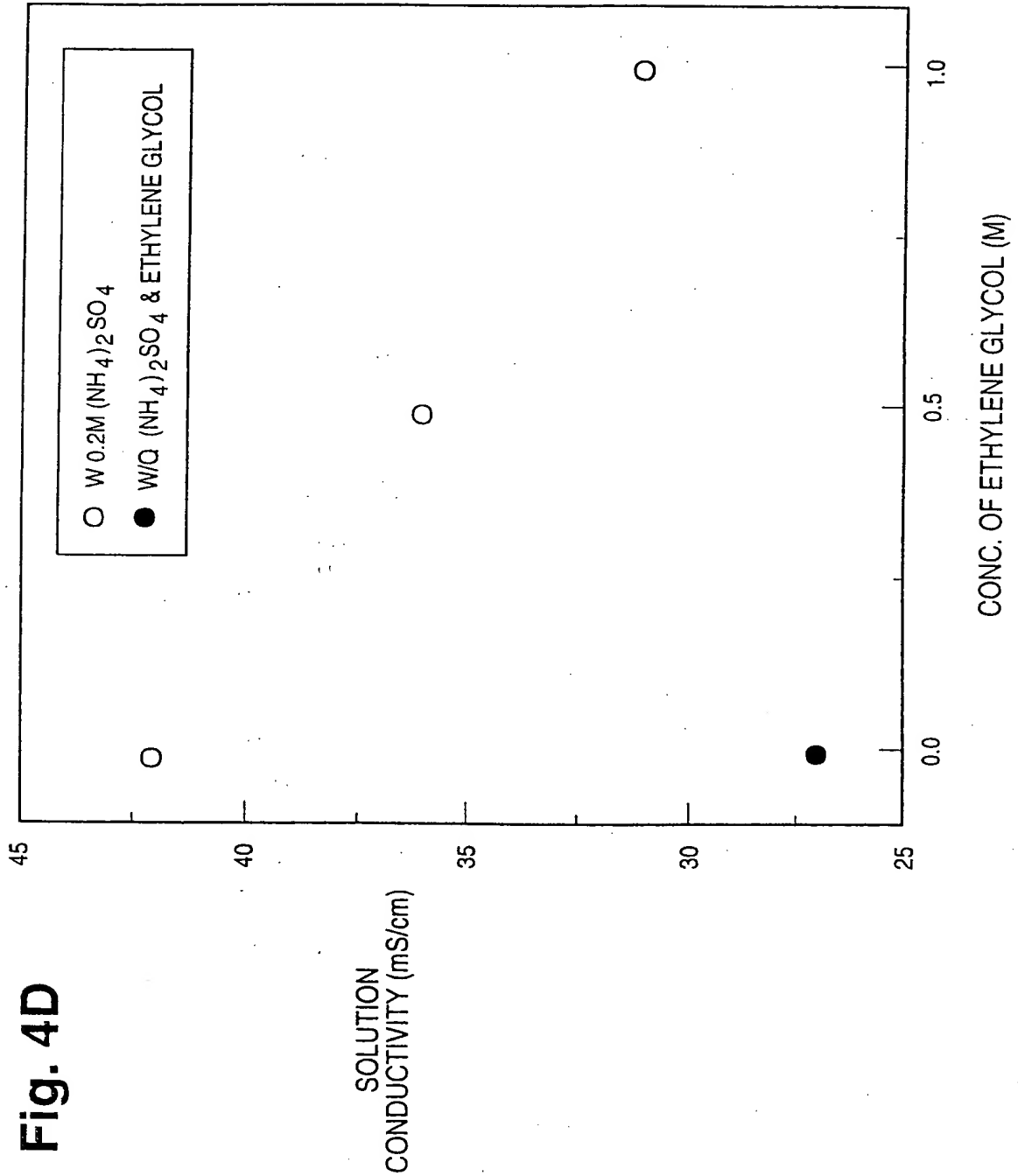
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Title: APPARATUS AND METHOD FOR
ELECTROLYTICALLY DEPOSITING COPPER ON
SEMICONDUCTOR WORKPIECE

Inventor: L. Chen
Docket No.: SEMT117581

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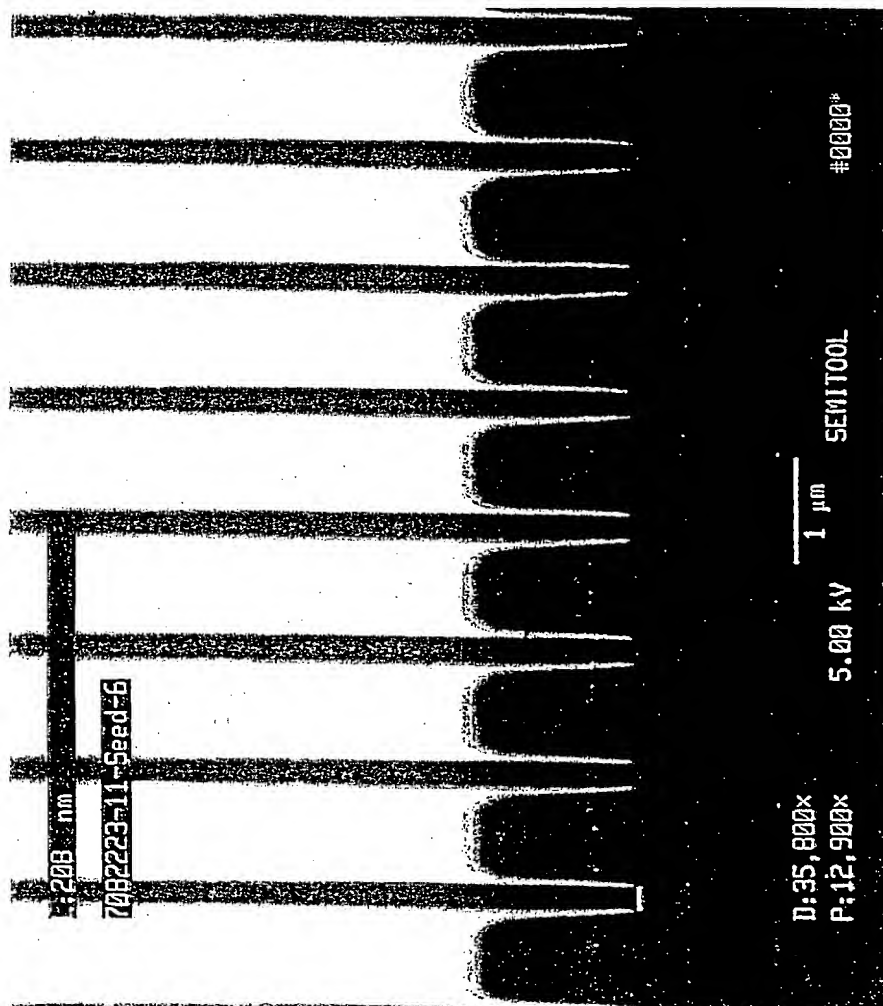


Fig. 5

: APPARATUS AND METHOD FOR
CTROLYTICALLY DEPOSITING COPPER A
SEMICONDUCTOR WORKPIECE

Inventor: L. Chen
Docket No.: SEMT117581

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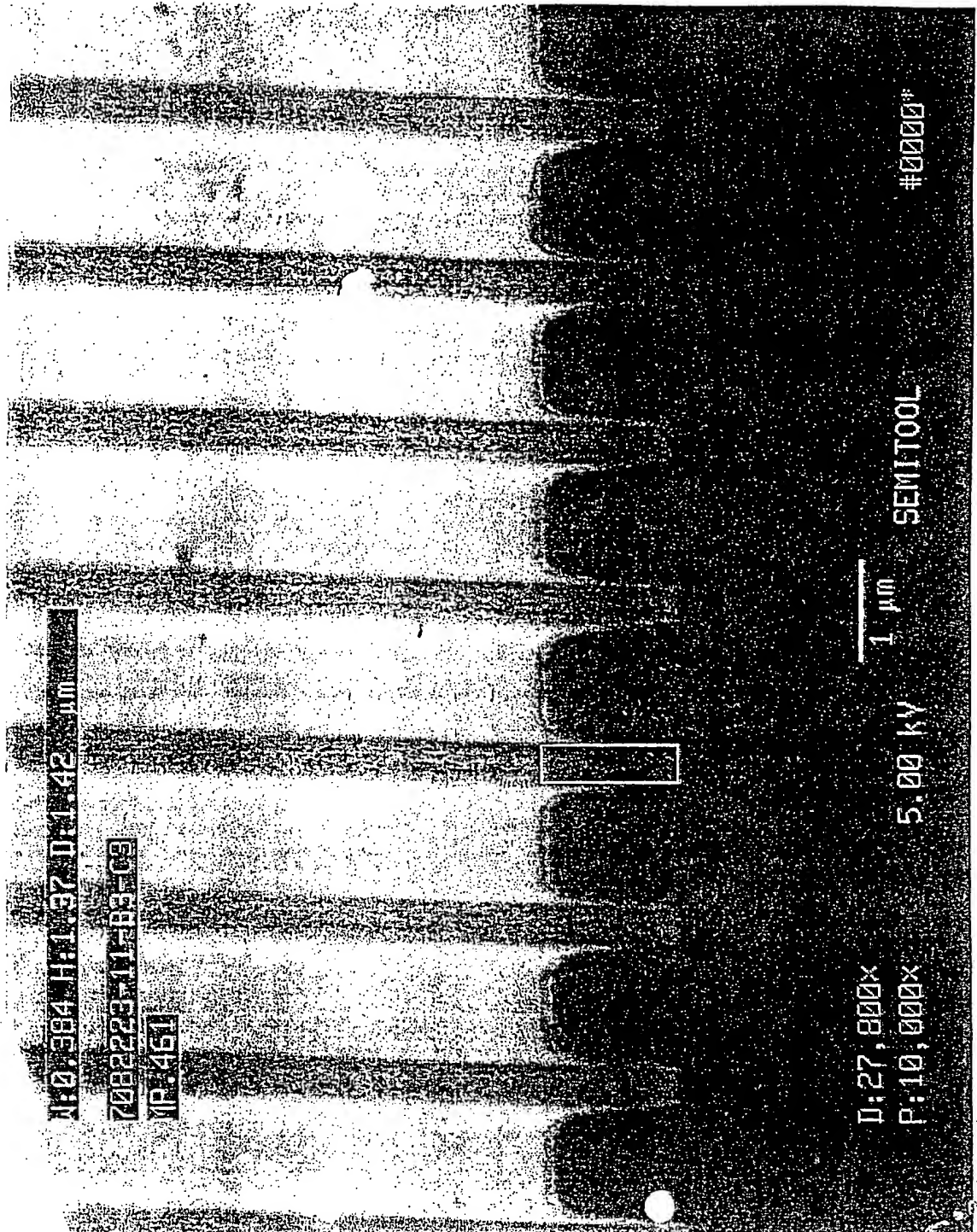


Fig. 6A

APPARATUS AND METHOD FOR
ELECTROLYTICALLY DEPOSITING COPPER ON A
SEMICONDUCTOR WORKPIECE

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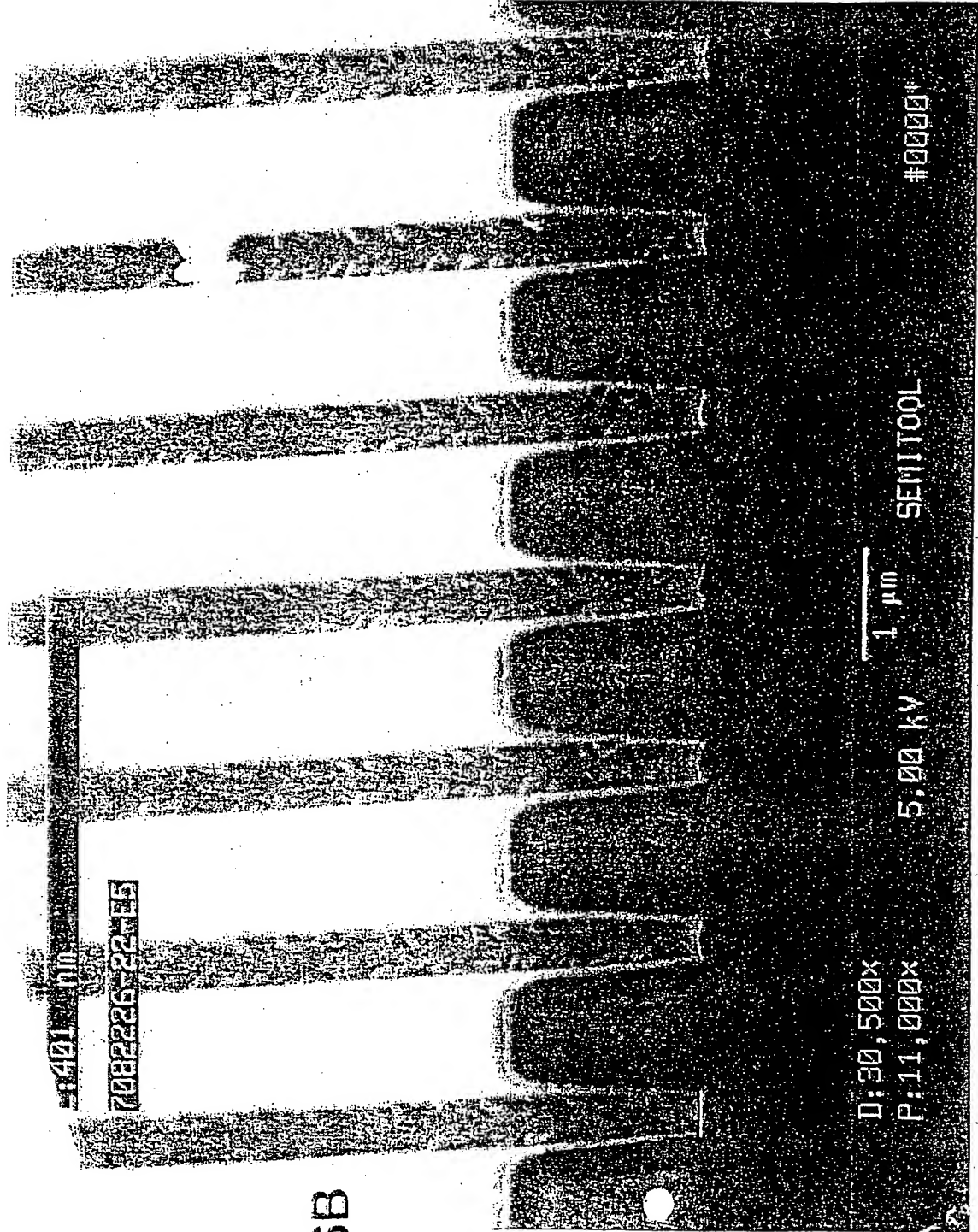


Fig. 6B

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Fig. 7

